

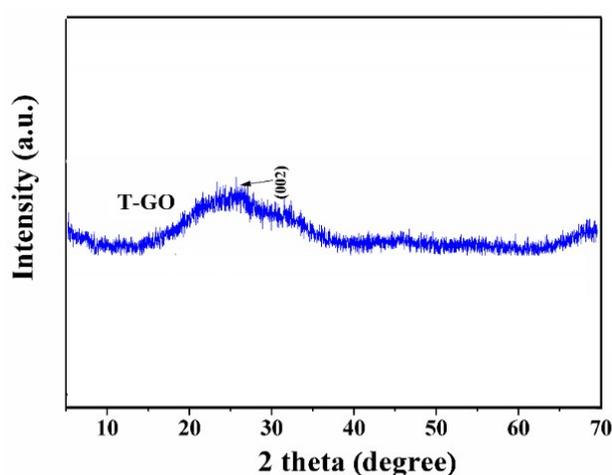
## Supplementary data

# A reduced graphene oxide-NiO composite electrode with a high and stable capacitance

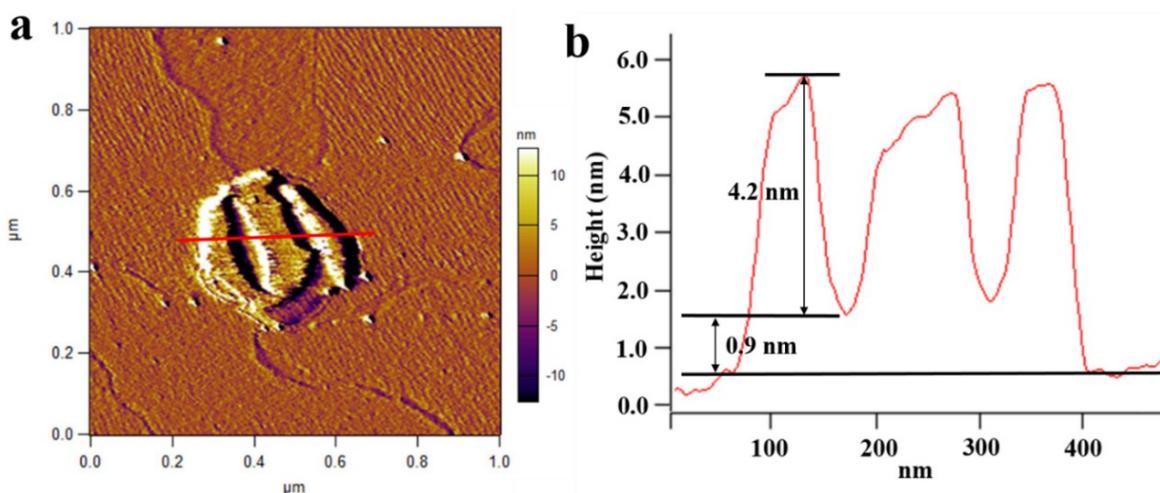
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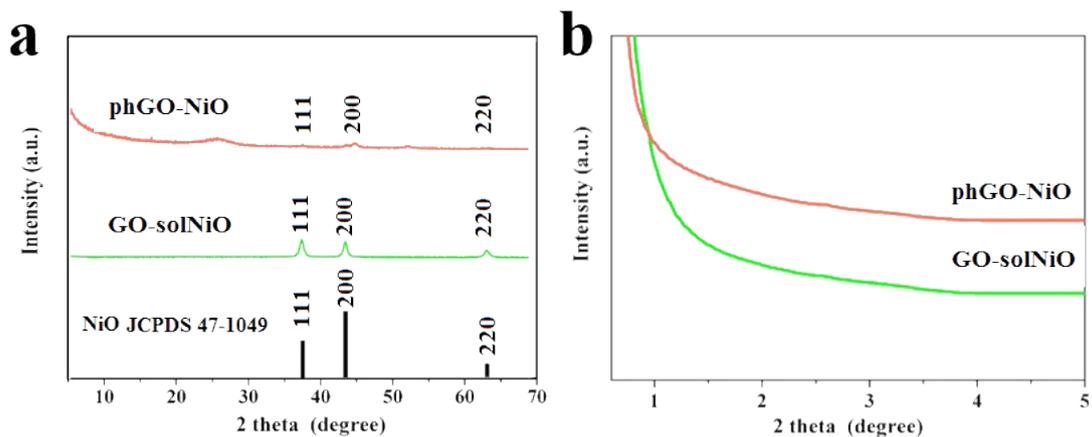
*Correspondence to [george.zhao@uq.edu.au](mailto:george.zhao@uq.edu.au).*



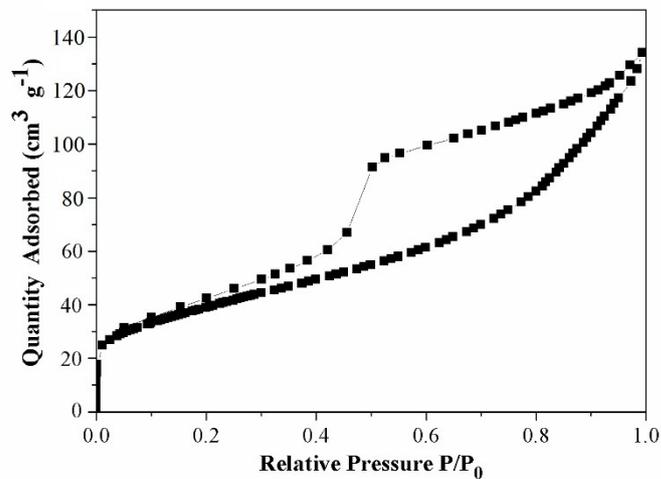
*Figure S1 XRD pattern of T-GO.*



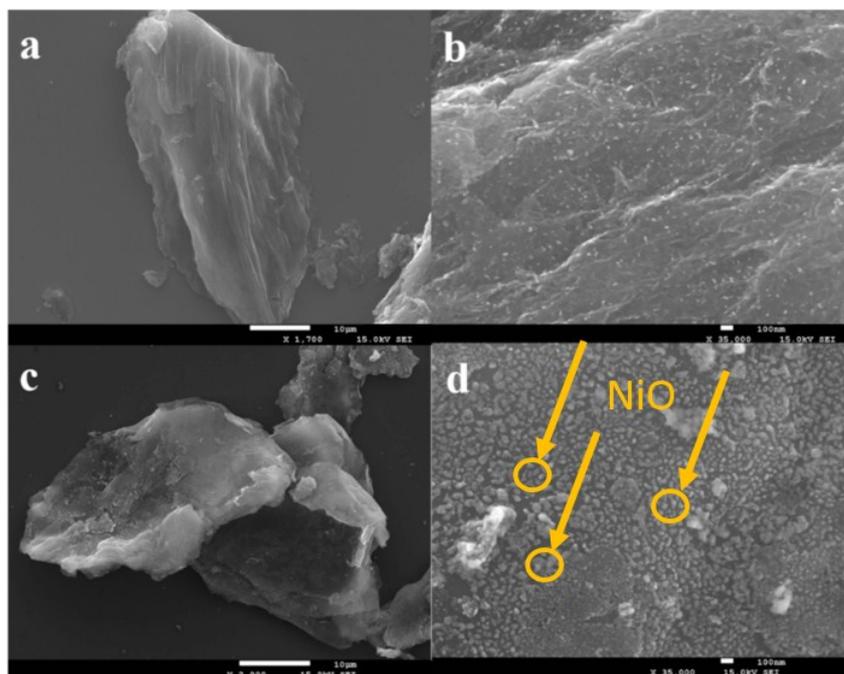
*Figure S2 (a) AFM image of nickel oxide nanoparticles on RGO from EGO-NiO and (b) cross-section thickness contour.*



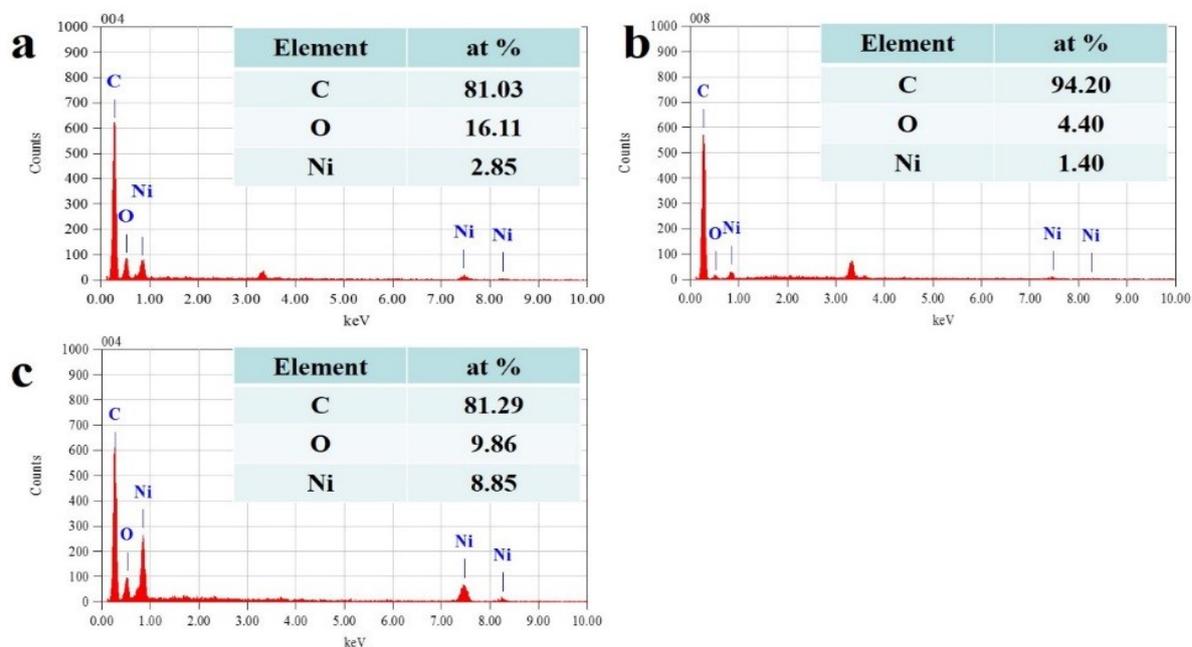
**Figure S3** (a) XRD patterns of GO-solNiO and phGO-NiO and (b) small-angle XRD patterns of GO-solNiO and phGO-NiO.



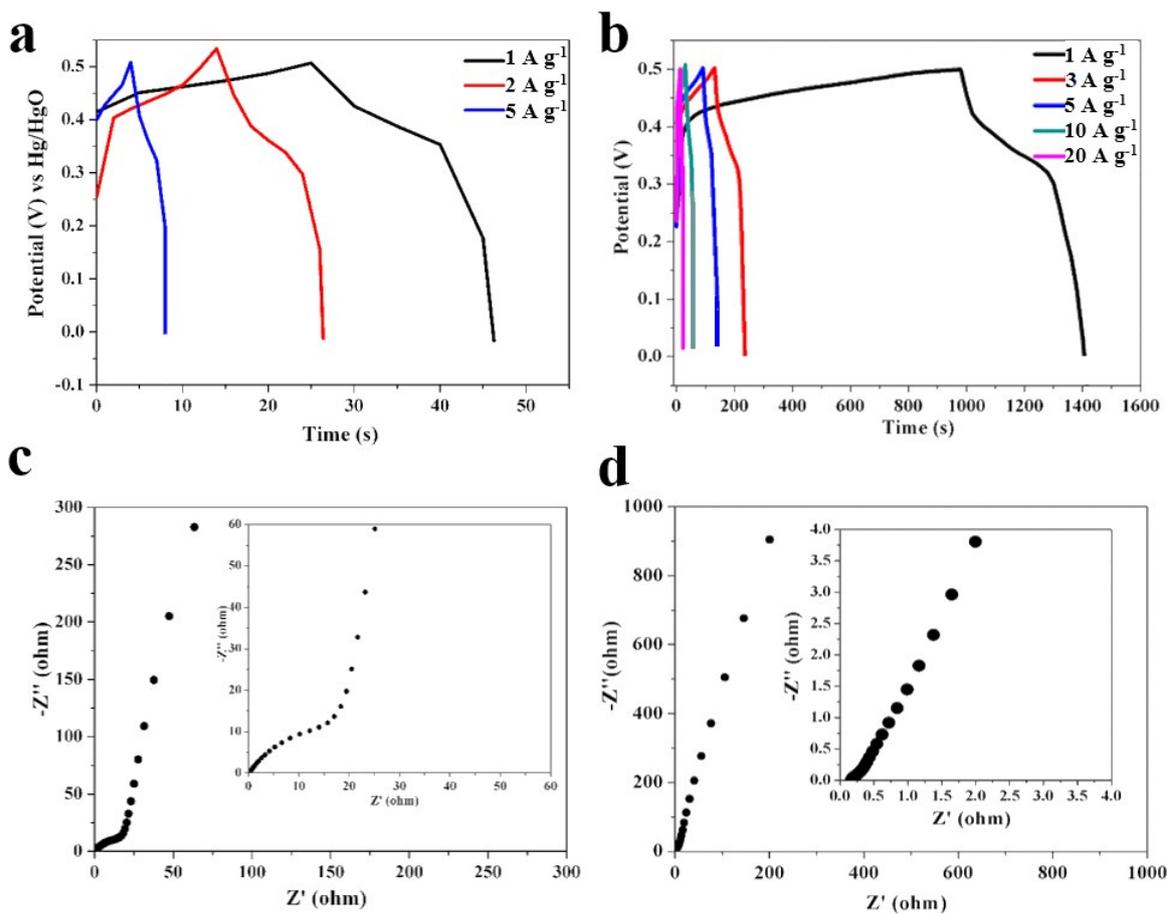
**Figure S4**  $N_2$  adsorption-desorption isotherm of EGO-NiO.



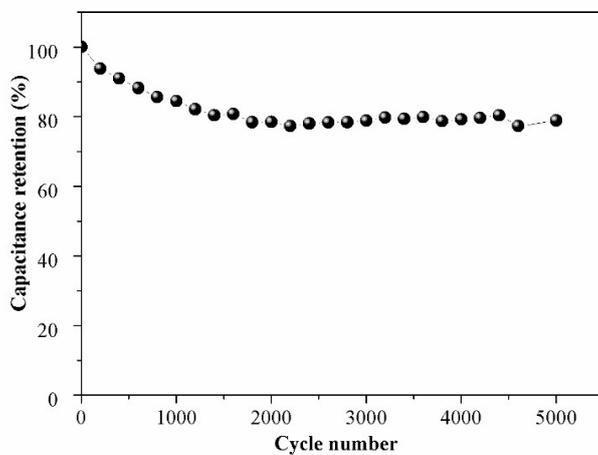
**Figure S5** SEM images in low and high magnifications of GO-solNiO (a, b) and phGO-NiO (c, d).



**Figure S6** SEM-EDS data of (a) EGO-NiO, (b) GO-solNiO and (c) phGO-NiO.



**Figure S7** GCD curves at different current densities of pristine GO (a) and EGO-NiO (b), Nyquist plots of GO (c) and EGO-NiO (d). The insets in Figures S6 c and d show high-frequency Nyquist plots.



**Figure S8** Cycling performance of EGO-NiO for 5000 cycles at 20 A g<sup>-1</sup>

*Table S1 Comparison of NiO-based pseudocapacitive electrode materials*

<b>Materials</b>	<b>Preparation method</b>	<b>Specific capacitance <math>C_s</math> (<math>F \cdot g^{-1}</math>)</b>	<b>Cycle stability (%, cycle numbers)</b>
<b>NiO-reduced graphene oxide (this work)</b>	Vacuum-thermal treatment	880 at 1 A $g^{-1}$	84%, (1000) at 20 A $g^{-1}$
<b>NiO film</b> <sup>54</sup>	Chemical bath deposition + template removal	309 at 1 A $g^{-1}$	89%, (4000) at 1 A $g^{-1}$
<b>NiO/Graphene</b> <sup>55</sup>	Vacuum promoted low-temperature heat treatment	220 at 0.1 A $g^{-1}$	100%, (1000) at 2 A $g^{-1}$
<b>NiO/ultrathin derived graphene</b> <sup>56</sup>	Nanocasting + chemical bath deposition	425 at 2 A $g^{-1}$	79%, (2000) at 10 A $g^{-1}$
<b>NiO/nanoporous graphene</b> <sup>57</sup>	Atomic layer deposition	1005.8 at 1 A $g^{-1}$	94%, (1500) at 2 A $g^{-1}$
<b>NiO/3D graphene</b> <sup>58</sup>	CVD + electrochemical deposition	745 at 1.4 A $g^{-1}$	100%, (2000) at 80 mV $s^{-1}$